

Biography

Annelies Delabie obtained a master degree in chemistry in 1997, and a PhD degree in science in 2001 from the KU Leuven (University of Leuven) in Belgium. In 2001, she joined imec, the research institute for nano-electronics and nanotechnology in Belgium. As principle member of technical staff, she investigates the fundamentals and applications of thin films and their deposition techniques, with a focus on Atomic Layer Deposition (ALD) and Chemical Vapor Deposition (CVD). Since 2012, she is also appointed associate professor at the chemistry department of the KU Leuven, where she started the research group “Nano-engineered Thin Films”. She is a member of the American Vacuum Society (AVS) ALD conference committee. She is (co-) author of 9 patents and more than 180 scientific publications in peer reviewed journals.

